

## ABSTRACT

An optical waveguide-forming material is comprised of  
5 a photocurable organopolysiloxane composition comprising an  
alkali-soluble organopolysiloxane and a photoacid generator,  
wherein the organopolysiloxane is obtained by (co)hydrolytic  
condensation of a triorganoxysilane having hydrolyzable  
epoxide and has an average molecular weight of 500-50,000 as  
10 determined by GPC using polystyrene standards. The optical  
waveguide-forming material, when subjected to pattern  
formation by photolithography, can be resolved with an  
alkaline aqueous solution, has a high sensitivity and  
resolution, and offers a cured film having improved light  
15 transmittance, heat resistance and humidity resistance.